

A free-standing lithium phosphorus oxynitride thin film electrolyte promotes uniformly dense lithium metal deposition with no external pressure

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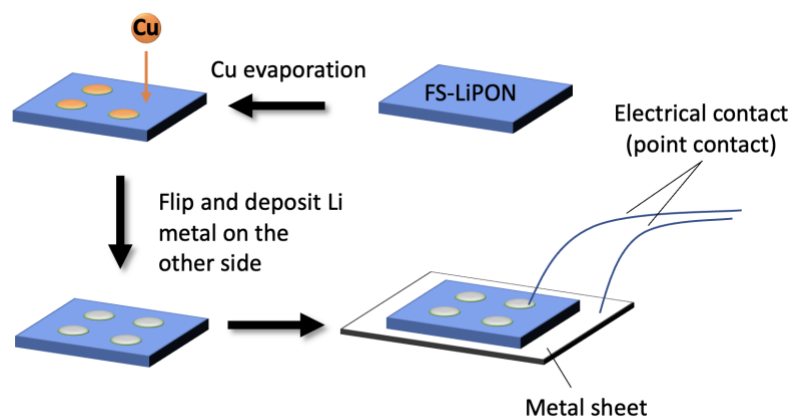
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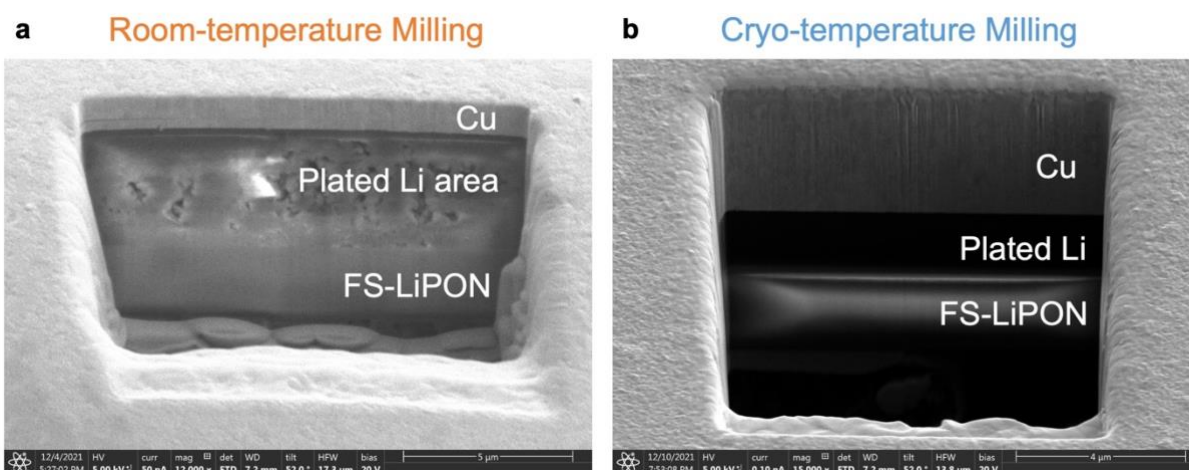
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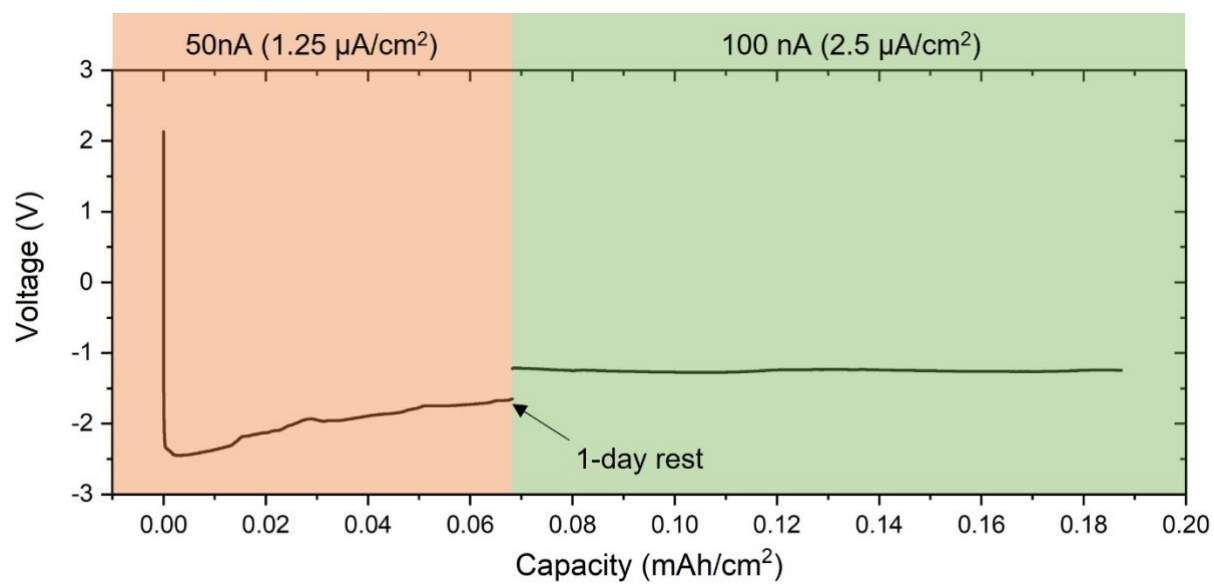
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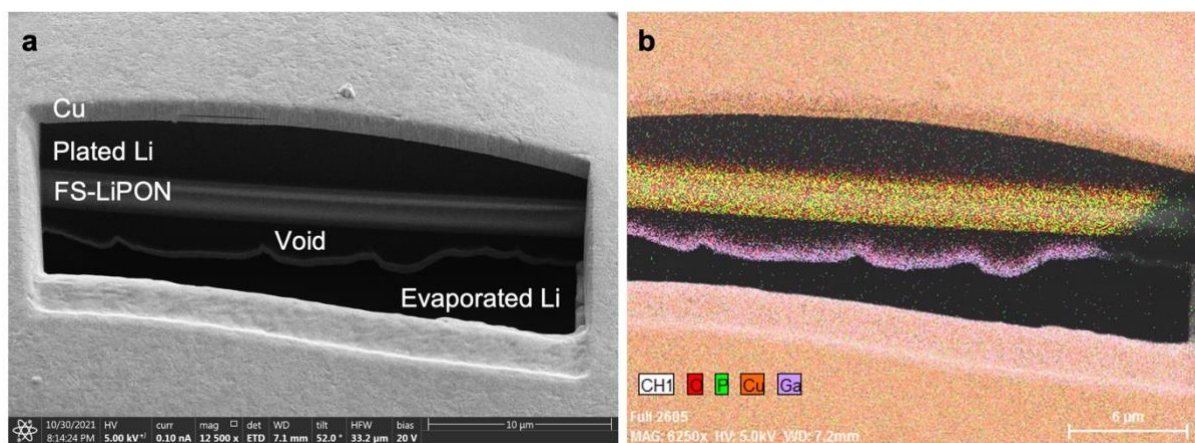
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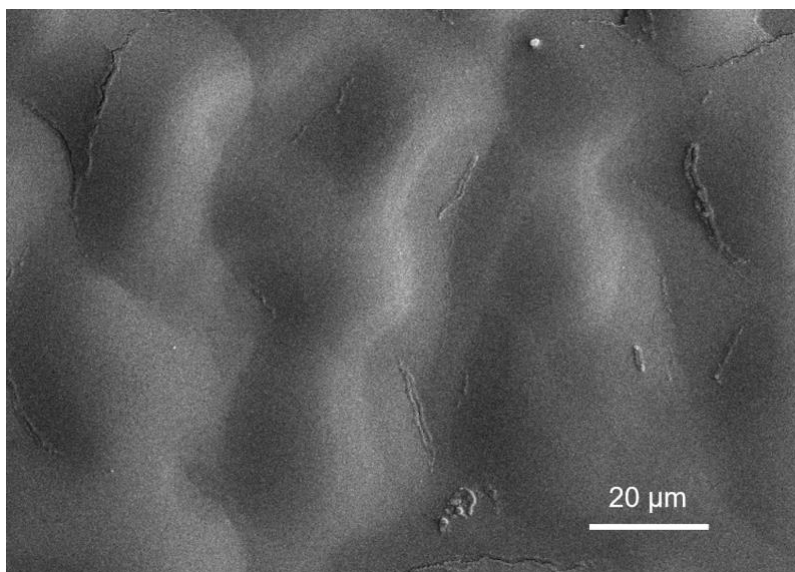
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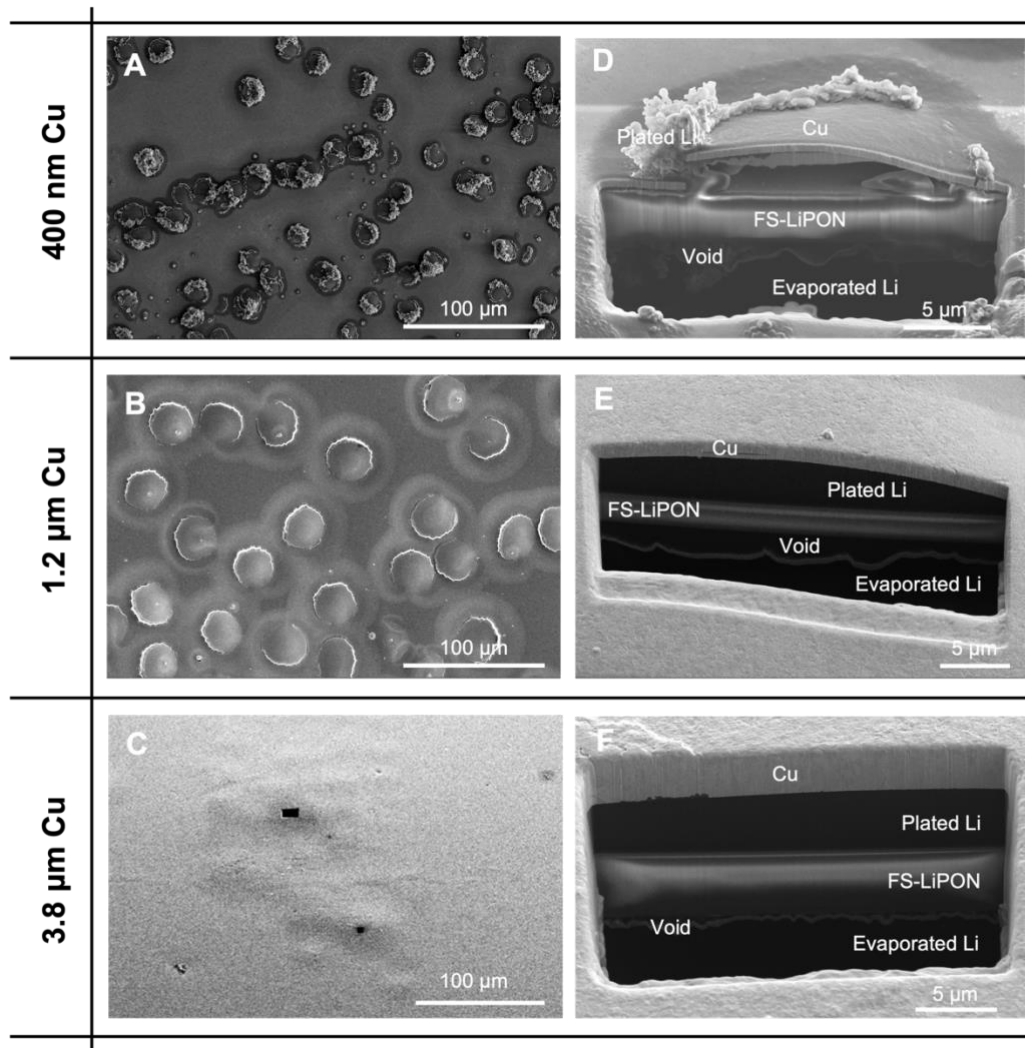
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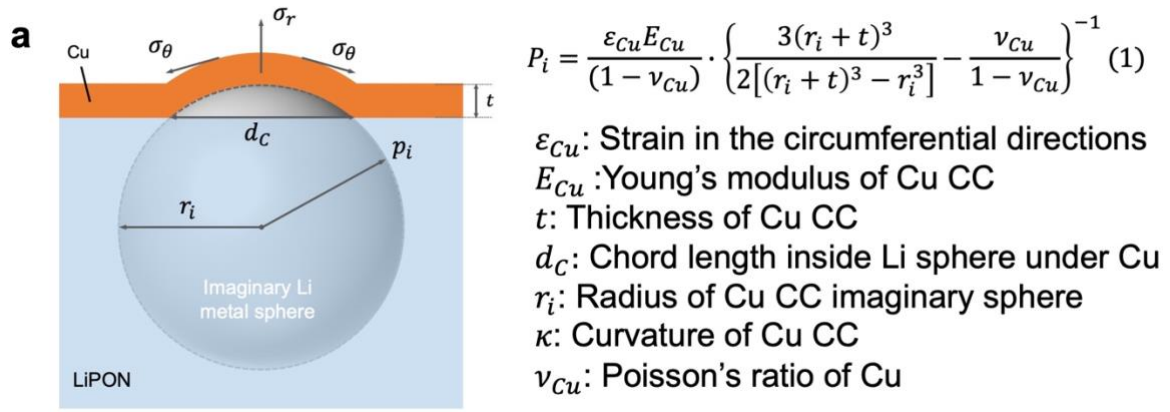
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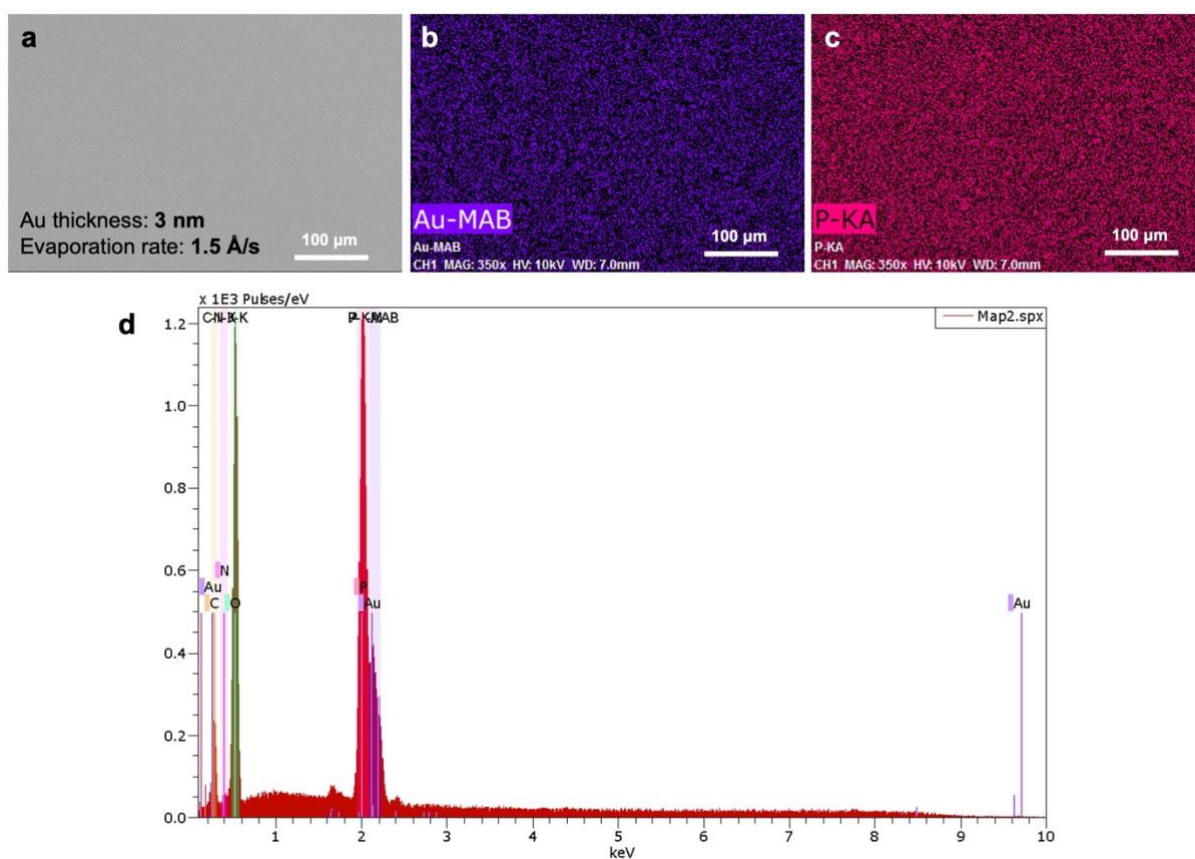


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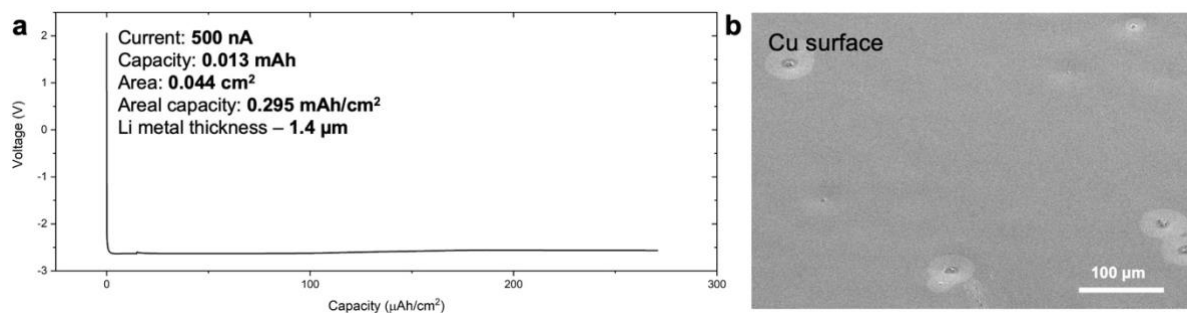


	400 nm Cu	1.2 μm Cu	3.8 μm Cu
ε_{Cu}	0.052	0.030	0.024
E_{Cu} / GPa	130	130	130
t / μm	0.4	1.2	3.8
r_i / μm	16.036	54.054	227.273
ν_{Cu}	0.34	0.34	0.34
$P_i (= \sigma_r)$ / GPa	0.503	0.260	0.151

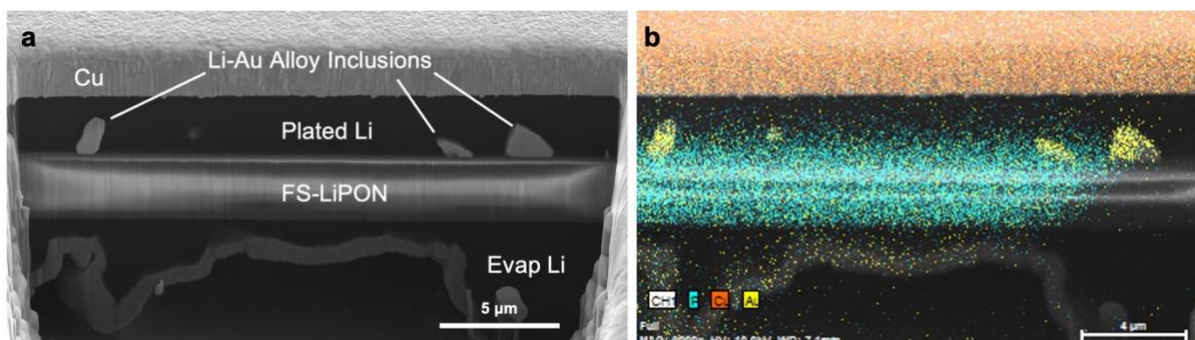
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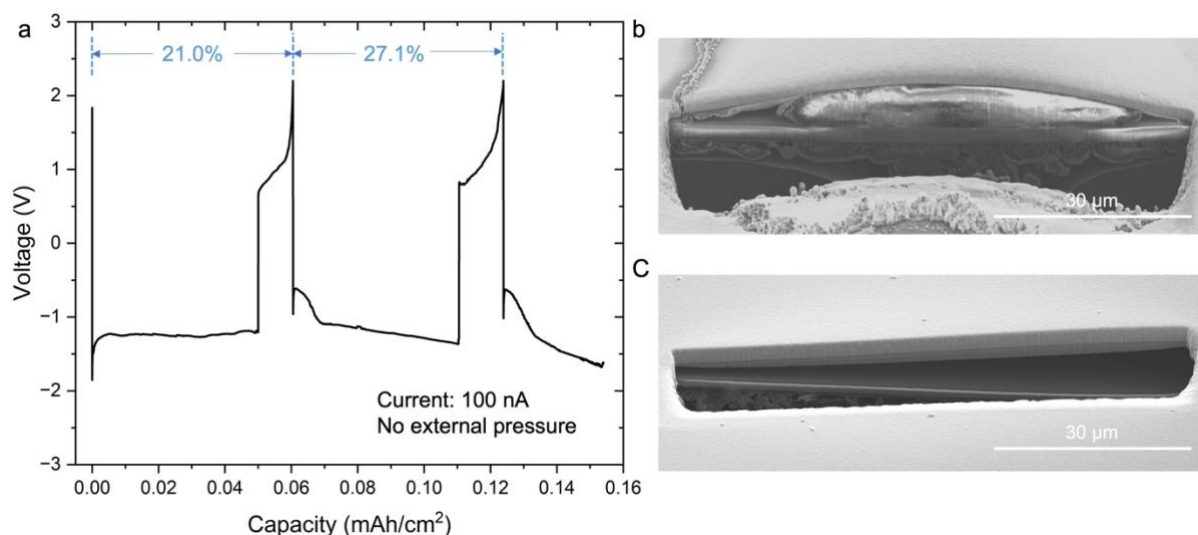
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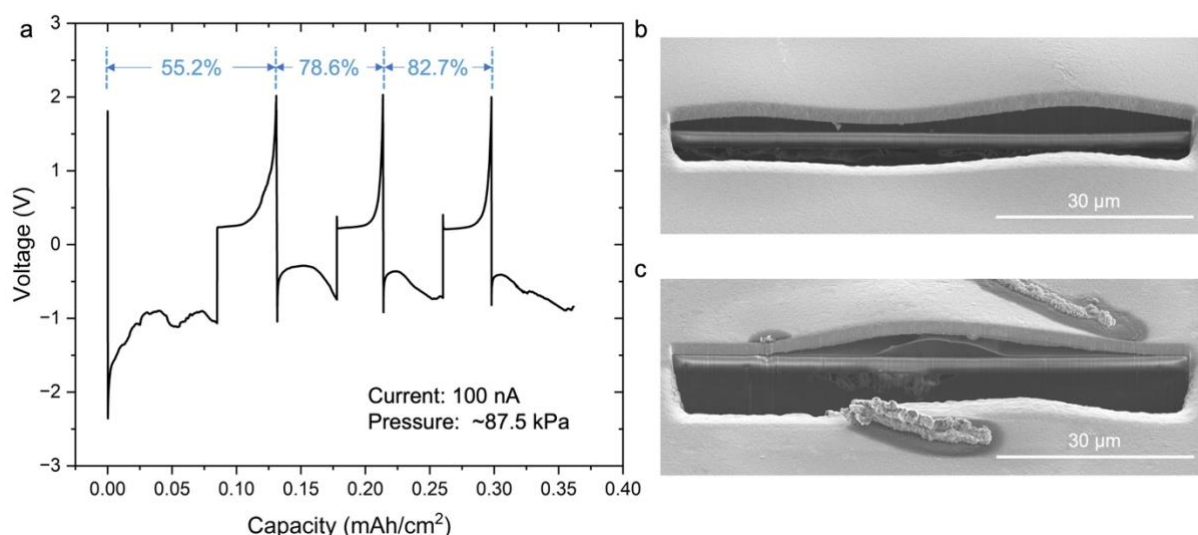
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As Fig. S12A shows below, a Li-Cu cell was plated with 50 $\mu\text{Ah}/\text{cm}^2$ of Li metal in the first cycle that corresponds to a Li metal thickness of 250 nm. However, the first stripping efficiency appeared quite low as only 21%. Another cycle gave a slightly higher Coulombic efficiency of 27.1%, which is still low. The cell morphology was examined afterwards as Fig. S11B & C show. In Fig. S11B, Cu surface deforms to large bumps. Li metal cross section appeared charging under SEM, which indicates Li metal has reacted with atmosphere due to the cleavage of Cu current collector. Fig. S11C further shows a large gap generated under Cu surface after repeated Li plating/stripping, suggesting the stripping was not uniform. In order to improve the stripping uniformity, we applied external pressure of ~87.5 kPa on the cell during plating and stripping. Fig. S12A shows the voltage curve of Li-Cu FS-LiPON cell with the external pressure present. In contrast to Fig. S12A, Li-Cu cell here shows a much higher initial Coulombic efficiency of 55.2%, which ramped up to 82.7% during the third cycle. Such improvement is likely caused by the external pressure that assisted Cu to deform back when Li metal was being stripped away. We further checked the cell morphology afterwards. Fig. S12B shows the dense Li metal cross section after repeated cycling with external pressure. However, we did observe gap formation underneath Cu as Fig. S12C shows, which is in consistence with the Coulombic efficiency trend. Note that the gap was formed between Cu and FS-LiPON, which led to the disconnection of electron pathway and caused the residual inactive Li metal. This indicates that the external pressure is playing a more important role during stripping process. And by using external pressure we could largely improve the cell performance for repeatedly cycling.